

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE				ATTY. DOCKET NO. MI22-1904		PRIORITY SERIAL NO. 02/843,446		
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Michael Nutall et al.		10/050426		
				PRIORITY FILING DATE April 24, 2001		PRIORITY GROUP 2813		
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name		Class	Subclass	Filing Date If Appropriate
	AA	4,497,683	02/1983	Celler et al.		156	603	
	AB	4,963,506	10/1990	Liaw et al.		438	482	
	AC	5,080,933	01/1992	Grupen-Semantky et al.		427	255.1	
	AD	5,110,757	05/1992	Arst et al.		438	489	
	AE	5,124,276	06/1992	Somara et al.		438	607	
	AF	5,364,815	11/1994	Osada		438	489	
	AG	5,441,012	08/1995	Aketagawa et al.		117	86	
	AH	5,006,911	04/1991	Sivan		357	23.11	
	AI	5,818,100	10/1998	Grider et al.		257	616	
	AJ	5,037,775	08/1991	Reisman		437	89	
	AK	5,646,073	07/1997	Grider et al.		437	233	
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	
	AL						No	
	AM							
	AN							
	AO							
	AP							
.HER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AR			Violette, Kathy, et al., "Low Temperature Selective Silicon Epitaxy by Ultra High Vacuum Rapid Thermal Chemical Vapor Deposition Using Si ₂ H ₆ H ₂ and Cl ₂ ", Appl. Phys. Lett., Vol. 68(1), pp. 66-68 (January 1996).				
	AS			Wolf, Stanley, et al., "Chemical Vapor Deposition of Amorphous and Polycrystalline Films, Silicon Processing for the VLSI Era", Vol. 1: Process Technology, pp. 183 and 191 (Lattice Press).				
	AT							
EXAMINER	<i>Barrett</i>			DATE CONSIDERED	<i>8/11/04</i>			
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE					ATTY. DOCKET NO. MI22-1904	PRIORITY SERIAL NO. 00-043,116		
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Michael Nutall et al.	10/050 426		
					PRIORITY FILING DATE April 24, 2001	PRIORITY GROUP 2613		
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Relevant Appropriate	
	AA	6,013,575	01/2000	Itoh	438	64		
	AB	4,948,755	08/1990	Mo	437	195		
	AC	4,966,868	10/1990	Murali et al.	437	193		
	AD	5,607,878	03/1997	Otsuka et al.	437	187		
	AE	5,663,098	09/1997	Creighton et al.	438	675		
	AF	6,017,823	01/2000	Shishiguchi et al.	438	696		
	AG	6,069,036	09/2000	Kim	438	238		
	AH	5,798,278	08/1998	Chen et al.	437	43		
	AI	5,037,778	08/06/91	Reisman	437	89		
	AJ							
	AK							
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
	AL						Yes	No
	AM							
	AN							
	AO							
	AP							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AR							
	AS							
	AT							
EXAMINER				DATE CONSIDERED				
<i>Barrell</i>				<i>10/10/04</i>				
<small>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with NPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>								